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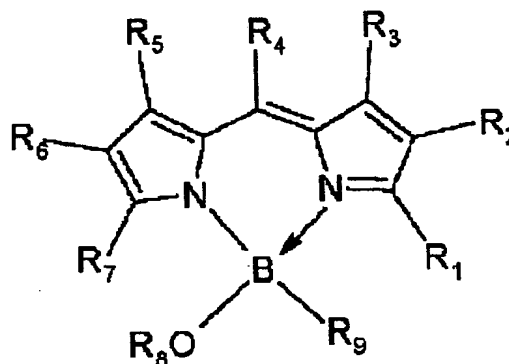
APPLICATION DATE : 07-07-98
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APPLICANT : MITSUI CHEMICALS INC;

INVENTOR : TAKUMA HIROSUKE;

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H01L 21/027 // C07F 5/02 C09K 3/00

TITLE : POSITIVE VISIBLE LIGHT SENSITIVE
RESIN COMPOSITION AND
APPLICATION THEREOF



ABSTRACT : PROBLEM TO BE SOLVED: To provide a composition containing a photosensitizer excellent in preservation stability and high in sensitivity to laser beams of long wavelength by containing a specific dipyrromethene boron complex as the photosensitizer.

SOLUTION: This composition contains a dipyrromethene boron complex expressed by a formula, as a photosensitizer. This photosensitizer is excited by absorbing light in a visible light area of 400-700 nm, particularly 400-600 nm, and interacts with resin and a photo-acid generating agent. In the formula, R_1 - R_7 independently represent hydrogen atom, halogen atom, nitro group, cyano group, hydroxy group, amino group, carboxyl group, sulfonic acid group, alkyl group, halogenoalkyl group, alkoxyalkyl group or the like; R_4 represents hydrogen atom, cyano group, alkyl group, aralkyl group, aryl group, heteroaryl group or the like; R_8 represents alkyl group, aryl group or aralkyl group; and R_9 represents halogen atom, alkoxy group, aryloxy group or the like.

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